Supplemental Information

Molecular Layer Deposited Hf-Based Hybrid Photoresists for Dual-Tone EUV Lithography

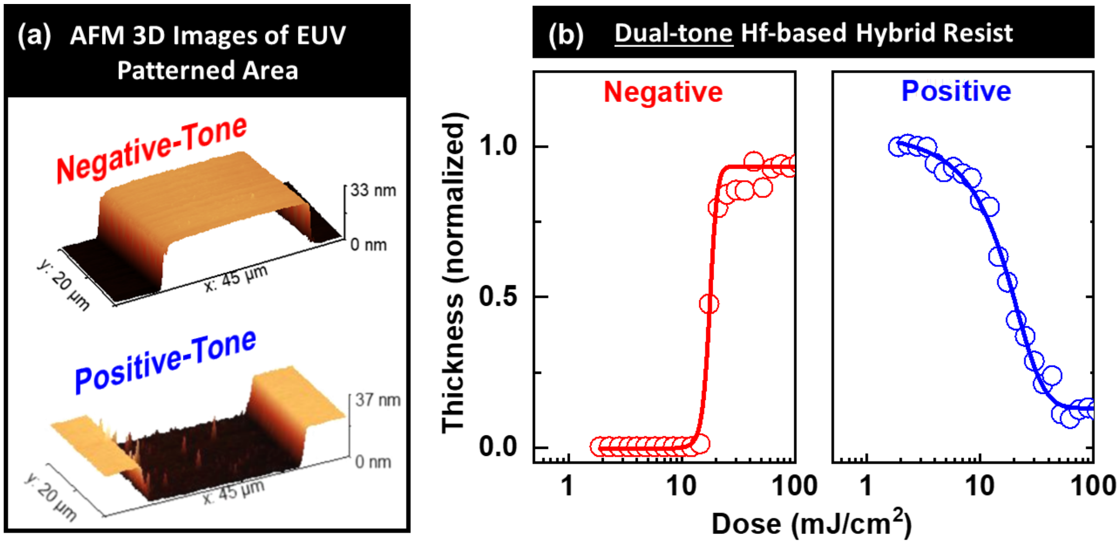

Figure 1. (a) 3D AFM images of EUV-patterned areas in negative- and positive-tone modes. **(b)** EUV contrast curves obtained from AFM analysis of the Hf-based hybrid resist.